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ABSTRACT OF THE DISCLOSURE

A resin with low polydispersity index and a process for preparing the same. The process includes polymerizing at least one monomer with an initiator and a chain transfer reagent, wherein the monomer is an acrylate monomer having at least one ethylenically unsaturated bonds or norbornene derivatives. Furthermore, a photoresist composition containing the resin composition according to the present invention can increase pattern resolution in lithography process.